

2016 Q4 Quarterly Reliability Report

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1. Introduction

Cypress's Reliability Monitor Program (RMP) is used to measure the reliability of all process technologies on a regular basis. This is an extensive effort that is aimed at providing generic fab process coverage for all fab process technologies.

The Reliability Monitor Program has two purposes:

1. Improved Reliability Performance

Each reject is analyzed to its root cause in order to drive continuous improvement through the implementation of corrective actions.

2. Generation of Reliability Data

RMP test results are used to assess the benefits of burn-in, provide estimates of typical lifetimes, model field applications, and determine suitability of plastic packaging in various temperature and humidity environments.

A number of process technology groupings are established for the purpose of reliability assessment. These groupings result in larger sample sizes so that the reliability analysis is statistically significant. Process similarity guidelines are used to define these process groupings.

Cypress Semiconductor has established aggressive reliability objectives. The quality standard at Cypress is zero defects, driven by a culture requiring continuous improvement in quality and reliability.

Product reliability is assured by a total quality management system. The quality management system is described in detail in Cypress Semiconductor Quality Manual. Key reliability related programs of the total quality management system are: (1) design rule review and approval; (2) control of raw materials and vendor quality; (3) manufacturing statistical process controls; (4) "Maverick Lot" yield limits; (5) formal training and certification of manufacturing personnel; (6) qualification of new products and manufacturing processes; (7) continuous reliability monitoring; (8) formal failure analysis and corrective action; and (9) competitive benchmarking.

Product Reliability data is accumulated as a result of new product qualification test plan activities as well as from the reliability monitor program. All reliability test samples are obtained from standard production material. Sample selection is based on generic product families. These generic products are designed with very similar design rules and manufactured from a core set of processes. Sampling of device is not limited to in-house Cypress facilities but also includes certified external subcontractor foundries.

Reliability strategy requires that every failure that occurs during reliability testing be subjected to failure analysis to determine the failure mechanism. Corrective action is then implemented to prevent future failures, resulting in continuous improvement in product reliability.

> Sabbas Daniel Executive Vice-President, Quality

2. Reliability Tests and Test Conditions

The results of the RMP testing for the past six quarters are summarized in this document. The stress tests employed and the typical test conditions used are shown in the [Table 2.1.](#page-3-1)

| Stress | Ambient Condition | Typical Read Point |
|---------------------------------|------------------------------|---------------------------|
| Early Life | 150°C, 125°C | 48, 96 hours |
| Inherent Life | 150°C, 125°C | 168, 408, 500, 1000 hours |
| Data Retention | 150°C, 125°C | 1000 hours |
| HAST | 110°C, 85% RH | 264 hours |
| | 130°C, 85% RH | 96 hours |
| Temperature Cycle | -40°C to 150°C (Condition M) | 1000 cycles |
| | -55°C to 125°C (Condition B) | 1000 cycles |
| | -65°C to 150°C (Condition C) | 500 cycles |
| Unbiased HAST | 110°C, 85% RH, no bias | 264 hours |
| | 130°C, 85% RH, no bias | 96 hours |
| Pressure Cooker Test | 121°C, 15 PSIG, no bias | 96, 168 hours |
| High Temperature Storage | 150°C, 125°C | 1000 hours |

Table 2.1 Reliability Monitor Stress Conditions

Package level reliability testing refers to the assessment of the overall reliability of the device in packaged form. This consists of subjecting packaged samples to reliability tests that exposed the sample sets to different stress conditions, after which the samples are tested for any degradation.

At Cypress, plastic surface mount devices are pre-conditioned prior to undergoing Temperature Cycling, Pressure Cooker Test/Unbiased HAST, and HAST. Pre-conditioning per JEDEC Standard JESD22-A113 is required in order to simulate the stresses to which the packaged parts are subjected to during shipping, storage, board assembly and cleaning operations. Package reliability tests are performed as part of the qualification processes and as part of the standard reliability monitor program. The reliability test employed is chosen based on the failure mechanism, as different stress tests accelerate different failure mechanisms. These reliability tests utilize one or more of the following stress factors such as: temperature, moisture or humidity, voltage and pressure, to accelerate failure. Figure 2.1 shows Cypress package reliability stress flow. Packages are soaked and reflowed based on their shipping moisture sensitivity classification. The samples are tested (acoustic and electrical) after preconditioning, failures from which are considered as preconditioning failures and not reliability failures. Preconditioning failures should be taken seriously, since these imply that the samples are not robust enough to withstand the board mounting process.

Figure 2.1 Cypress Package Reliability Stress Flow

3. Reliability Data/Analysis

The reliability data generated from the Reliability monitor Program is presented in this section along with a detailed description of the modeling procedure used for estimating reliability under field conditions. Also included is a summary of environmental stress results for each process technology grouping by package types.

3.1 The Exponential Distribution

The exponential distribution is simple to use, well understood and as valid as any for life tests with large sample sizes and few failures. No actual distribution can be implied as there is seldom enough data to determine one. The exponential distribution, characterized by a constant failure rate, is a special case of the Weibull. The average failure rate is the same as the instantaneous failure rate for the exponential distribution because the failure rate is constant.

The exponential distribution is the only one for which a MTTF (mean time to failure) value may easily be estimated and it is simply the reciprocal of the failure rate (λ) . In addition it is the only one for which a confidence level may be readily assigned to the failure rate calculation.

The conventional expression for the failure rate, λ , is

$$
\lambda = \chi^2 (2 n + 2, 1 - \alpha)^* 10^9 / (2^* S S^* t^* A F)
$$

where λ is the failure rate in FITs (failures per billion unit-hours), $\chi^2(2n+2,1-\alpha)/2$ is the upper confidence value for "**n**" failures and upper confidence limit, (expressed as a decimal value), **SS** is the sample size, t is the test duration in hours, and **AF** is the acceleration factor relating the life test junction temperature to a assumed field junction temperature.

The χ^2 (chi square) value for 2n+2 degrees of freedom and the probability, 1- α , can be obtained from a table or calculated using Microsoft® Excel chi squared inverse function [=CHIINV(1- α ,2n+2)].

The best way to understand the concept of confidence levels is to consider this example. Assume that a life test on a 100-part sample from a certain product population had one failure and a 60% confidence level was desired. The chi square value corresponding to one failure at 60% confidence is 2.02. This means that one has a 60% confidence that the "true" value of the population's defect rate is between zero (or some very small value) and 2.02%.

3.2 Failure Distributions

The lognormal and Weibull CDF's are the distributions most often used to represent reliability failure mechanisms. The exponential distribution, characterized by a constant failure rate, is a special case of the Weibull. The lognormal distribution is specified by two parameters: T_{50} , the median time to failure, and sigma, the shape parameter. Similarly, the Weibull distribution, which can be written in closed form as

$$
F(t) = 1 - \exp[-(t/c)^m],
$$

is characterized by a characteristic life c and a shape parameter m. The value of the shape parameter determines whether the failure rate is increasing (m>1), decreasing (m<1), or constant (m=1). The exponential distribution, is specified completely by the one parameter c which is called the mean time to failure (MTTF). Figures 1 and 2 show failure rates for several values of the scale parameters of the lognormal and Weibull distributions, respectively.

$$
F(t) = 1-\exp [-(t/c)],
$$

Figure 1. Lognormal Distribution

3.3 Calculations of Failure Rates

To estimate field failure rates from reliability studies, many factors must be considered. One primary requirement is the identification of individual failure mechanisms in order to ascribe the failures to the proper categories used in the Cypress reliability model.

3.3.1 Considerations and Assumptions

1. Defective subpopulations and Early Life failures:

In any production lot a defective subpopulation may exist. These are devices that fail by a mechanism that is not common to the general population and is usually the result of some processing error or defect. These failures usually occurs early and consequently called Early Life failures. Early life reliability is reported in terms of ppm defective expected during the first year of use under typical use conditions. No upper confidence bound will be used for this estimate. The ppm defective is the ration of the number of rejects to the number of samples and expressed in ppm.

PPM = (Total Reject / Total samples) * 1,000,000

2. Inherent Life failures:

Failures that occur in later life reliability are usually caused by mechanisms related to defects that could occur in any product of this type. These are known here as Inherent Life failures. Inherent life reliability is reported in using the exponential model, in terms of FITs (failures per billion unit-hours) with a 60% upper confidence bound for zero failure.

3. Estimation of thermal acceleration factors:

The best-known activation energies for each mechanism are used in calculating the thermal acceleration using the standard Arrhenius equation for thermal acceleration. For each process group/ package combination, representative acceleration factors were estimated based on the weighted average of acceleration factors of individual devices in that group.

- 4. Voltage acceleration factor is not included in failure rate calculation even though voltage acceleration may be used during stress.
- 5. It is common in reliability literature to see failure rates stated at a specified level of confidence:

For example, a 60% upper confidence limit on the failure rate indicates that unless a 4 in 10 chance (40%) has occurred, the true population failure rate is less than the stated limit. The summation of individual failure rate components, each at 60% confidence, will however, result in an overall failure rate at an unknown confidence level that may dramatically exceed 60%.The failure rates quoted in the Quarterly Reliability Report are at a 60% upper confidence level.

4. Data Summaries by Process Technology

4.1. S29CD-J, S29NS-J, S29PL-J, S71NS-J, S71PL-J Product Families

CS 69S, CS 69LS

This 0.11 micron CMOS Flash technology was introduced in December 2003 and utilizes a tunnel oxide, polysilicon floating gate, silicided poly word line and interconnections are three metal layers with contact plugs and barrier metal.

Data Summary and Failure Rate Estimation using Exponential Model HTOL Stress Temperature - 150°C

4.2. S29AL-J, S29AS-J, S29JL-J Product Families

CS 69SS, CS 69LSS

This 0.11 micron CMOS Flash technology was introduced in February 2008 and utilizes a tunnel oxide, polysilicon floating gate, silicided poly word line and interconnections are three metal layers with contact plugs and barrier metal.

Data Summary and Failure Rate Estimation using Exponential Model HTOL Stress Temperature - 150°C

4.3. S29GL-N, S29NS-N, S29PL-N, S29WS-N, S70PL-N, S71GL-N, S71NS-N, S71PL-N, S71WS-N Product Families

CS 119S, CS 119LS

This 0.11 micron CMOS Flash technology was introduced in June 2004 and utilizes a tunnel oxide, Silicon Nitride (SiN) data storage layer, silicided poly word line and interconnections are three or four metal layers with contact plugs and barrier metal.

Data Summary and Failure Rate Estimation using Exponential Model HTOL Stress Temperature - 150°C

4.4. S19FL-P, S25FL-P, S29GL-P, S29NS-P, S29WS-P, S70FL-P, S70GL-P, S71GL-P, S71NS-P, S71WS-P, S72NS-P Product Families

CS 129, CS 129L, CS 129AL

This 90 nanometer CMOS Flash technology was introduced in Aug 2006 and utilizes a tunnel oxide, Silicon Nitride (SiN) data storage layer, silicided poly word line and interconnections are three copper layers.

Data Summary and Failure Rate Estimation using Exponential Model HTOL Stress Temperature - 150°C

4.5. S29GL-S, S25FL-S S25FS-S, S26KL-S, S26KS-S Product Families

CS 239LS

This 65 nm Mirror bit flash technology was introduced in September 2010 and utilizes a tunnel oxide, Silicon Nitride (SiN) data storage layer, silicided poly word line and interconnections are four metal layers with contact plugs and barrier metal.

Data Summary and Failure Rate Estimation using Exponential Model HTOL Stress Temperature - 125°C

4.6. S25FL1-K, S25FL2-K Product Families

90 nm SPI Floating Gate

90 nm SPI (Serial Peripheral Interface) Floating Gate Flash Technology was introduced in May 2012 and utilizes tunnel oxide, polysilicon floating gate and interconnections are three metal layers with contact plugs and barrier metals.

Data Summary and Failure Rate Estimation using Exponential Model HTOL Stress Temperature - 150°C

4.7. S34ML-1 Product Families

48 nm SLC NAND

48 nm SLC NAND was introduced in July 2012 and utilize tunnel Oxide, Polysilicon floating gate and interconnections are three metal layers with contact plugs and barrier metals. The 1st Metal layer for 48 nm SLC NAND is using Tungsten.

Data Summary and Failure Rate Estimation using Exponential Model HTOL Stress Temperature - 125°C

4.8. S34ML-1 Product Families

41 nm SLC NAND

41 nm SLC NAND were introduced in Jun 2012 and utilize tunnel Oxide, Polysilicon floating gate and interconnections are three metal layers with contact plugs and barrier metals. The 1st Metal layer for 41 nm SLC NAND is using Copper.

Data Summary and Failure Rate Estimation using Exponential Model HTOL Stress Temperature - 125°C

4.9. S34ML-2 Product Families

32 nm SLC NAND

32 nm SLC NAND were introduced in October 2012 and utilize tunnel Oxide, Polysilicon floating gate and interconnections are three metal layers with contact plugs and barrier metals. The 1st Metal layer for 32 nm SLC NAND is using Copper

Data Summary and Failure Rate Estimation using Exponential Model HTOL Stress Temperature - 125°C

4.10. WUSB (CYRF6936*) Product Families

B53 Technology

Note:

***Insufficient data – interpret as insufficient accumulated life-time hours to project a 60%confidence bound for a zero-fails sample.*

4.11. HS_USB (CY7C65630*) Product Families

C8 Technology

4.12. FAST (CY7C1041D*) Product Families

C9 Technology

Note:

***Insufficient data – interpret as insufficient accumulated life-time hours to project a 60%confidence bound for a zero-fails sample.*

4.13. FAST (CY7C1041/61G*, CY62147/67G*), SYNC (CY7C1370K*, CY7C1441K*, CY7C1460/61K*) Product Families

LL65 Technology

4.14. Clocks (CY29430F) Product Families

LP55 Technology

4.15. HRBuffer (CY2305C) Product Families

R52 Technology

Note:

***Insufficient data – interpret as insufficient accumulated life-time hours to project a 60%confidence bound for a zero-fails sample.*

4.16. HRFAST (CY7C1019C*, CY7C1021C*, CY7C1041C) Product Families

R7 Technology

4.17. SYNC (CY7C1370D*, CY7C1380D*, CY7C1381D*) Product Families

R9 Technology

4.18. HRMPWR (CY62137F*, CY62128/46/47E*), MICROPWR (CY62147/57/67E*) Product Families

R95 Technology

4.19. CAPS (CY8C21534*), HRPSOC (CY8C24894*, CY8CTMA120*, CY8C22345*), LS_USB (CY7C64215*) Product Families

S4 Technology

4.20. CAPS(CY8C20236/20467*/CYTT21402*/4032*/CY8CTMA445*/CY8CTST242*); HRPSOC (CY8C4125/4245P*/4247A*, CYONSFN3050A*, CY8CTMA616A*, CYAT81688*); NVP (CY14V101P, CY14B101L/104N*), PSOC (CY8C4045A*/ 4128*/4146A*/42452A*/4246P*/4248A*/CY8CMBR3106*/3108*/31552*); TT (CYTMA450*), TYPE-C (CYPD21342*/4125*/4225*); WUSB (CYBL10462*/561*/563*, CYRF6936) Product Families

S8 Technology

Notes:

** 2u (Devices: CYTMA450/CYAT816882) - Non Visual Defect (NVD)*

- *Will be covered by Fab's continuous defect improvement*

*** 1u (Device: CYBL10563) - Wire to Wire Short*

- *CAR# 201530013: Optimized wirebond layout*

4.21. F-RAM (CY15B102/104Q*, FM25V20A*, FM25CL64B) Product Families

130nm TI F-RAM Technology

Data Retention Bake – 125/150°C

4.22. S6AP, S6BP, S6AE Product Families

180 nm PMICs

4.23. S6J3 Product Families

55 nm MCU (FLASH)

4.24. S6E2, MB9AF, MB91F Product Families

90 nm MCU (FLASH)

4.25. MB91, MB96 Product Families

180 nm MCU (FLASH)

5. Data Summaries by Package Family

5.1 BGA (Ball Grid Array)

5.2 BGA (Ball Grid Array) – Flip Chip

5.3 DFN (Dual Flat no-leads)

5.4 DIP (Dual Flat no-leads)

Note:

**1u (Device: CS6632AF, Assy Site: CML-RA) - Lifted Ball*

- *CAR# 201542014: Optimized wirebond parameter*

5.5 LCC (Leaded Chip Carrier)

5.6 QFN (Quad Flat no-leads)

5.7 QFP (Quad Flat Package)

5.8 SOJ (Small Outline J Lead)

5.9 SOP (Small Outline Gull Wing Lead Package)

Note:

5u (Device: CY2305CSXA, Assy Site: Amkor-Phils (M))*

2u - Lifted Ball - *CAR# 201529021: Optimized wirebond parameter*

3u – Cut Wedge

- *CAR# 201427001: Implemented new BOM (Bill of Material)*

*7u** (Device: CY2305CSXA, Assy Site: Amkor-Phils (M))*

- *1u - Lifted Ball*
	- *CAR# 201529021: Optimized wirebond parameter*

6u - Cut Wedge

- *CAR# 201427001: Implemented new BOM (Bill of Material)*

5.10 SSOP (Shrink Small Outline Package)

5.11 TSOP (Thin Small Outline Package)

Note:

**9u (Device: CY62167ELL, Assy Site: ASE-Taiwan (G)) - Lifted Ball*

- CAR# 201611019: Optimized wirebond parameter

5.12 WLCSP (Wafer Level Chip Scale Package)

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